

# STN:USPAT- Update - 6/3000

(FILE 'USPATFULL' ENTERED AT 14:08:05 ON 30 JUN 2000)

DEL HIS

L1 691 S CARBON(10A) IMPLANT?  
L2 24 S L1(P) (CMP OR POLISH? OR CHEMIPOLISH? OR CHEMIMECH? OR  
PLANARI  
L3 13 S L2(P) (SIO OR SIO2 OR SI3N4 OR NITRID? OR OXYNITRIDE? OR  
OXIDE  
L4 0 S L2(P) (POLYIMID? OR POLYAMID?)  
L5 2001 S C(3A) IMPLANT?  
L6 20 S L5(P) (CMP OR POLISH? OR CHEMIPOLISH? OR CHEMIMECH? OR  
PLANARI  
L7 10 S L6(P) (SIO OR SIO2 OR OXIDE# OR DIOXIDE# OR MONOXIDE# OR  
SI3N4  
L8 9 S L7 NOT L3

=> d his

STN<sub>g</sub> Cas Japis - Update - 6/2000

(FILE 'HOME' ENTERED AT 13:46:05 ON 30 JUN 2000)

FILE 'CA' ENTERED AT 13:46:09 ON 30 JUN 2000

L1 2216 S IMPLANT?(5A) (MASK# OR PHOTOMASK# OR RESIST# OR PHOTORESIST#)  
L2 20 S L1 AND (CMP OR POLISH? OR CHEMIPOLISH? OR CHEMIMECH? OR  
SLURR  
L3 23 S L1 AND PLANARIZ?  
L4 41 S L2 OR L3  
L5 28 S L4 AND (SIO OR SIO2 OR OXIDE# OR MONOXIDE# OR DIELECTRIC?  
OR  
L6 1 S L4 AND (SOG OR PSG OR BSG OR PBSG OR BPSG OR USG OR FSG OR  
NS  
L7 41 S L4 OR L5 OR L6  
L8 11405 S IMPLANT?(10A) (C OR CARBON#)  
L9 92 S L8 AND (CMP OR POLISH? OR PLANARIZ? OR SLURR? OR POLISH? OR  
C  
L10 2 S L9 AND ?STOP?  
L11 52 S L9 AND CARBON  
L12 2818 S CARBON(10A) IMPLANT?  
L13 50 S L11 AND L12  
L14 49 S L13 NOT L10  
L15 49 S L14 NOT L7  
L16 7 S L15 AND (INSULAT? OR DIELECTRIC? OR SIO OR SIO2 OR OXIDE#  
OR  
L17 13 S L15 AND (BPSG OR PBSG OR DIOXIDE# OR MONOXIDE# OR GLASS? OR  
?  
L18 18 S L16 OR L17  
L19 31 S L15 NOT L18  
L20 20 S L19 NOT (STEEL? OR CHROM?)  
L21 42 S L9 NOT L13  
L22 31 S L21 NOT (STEEL? OR CHROM?)  
L23 51 S L10 OR L13  
SAVE STOPL23/A L23  
DEL GRINDL4/A  
SAVE STOPL23/A L23  
SAVE STOPL7/A L7

FILE 'JAPIO' ENTERED AT 14:02:24 ON 30 JUN 2000

ACTIVATE STOPL23/A

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L24 QUE IMPLANT?(10A) (C OR CARBON#)  
L25 QUE L24 AND (CMP OR POLISH? OR PLANARIZ? OR SLURR? OR  
POLISH?  
L26 QUE L25 AND ?STOP?  
L27 QUE L25 AND CARBON  
L28 QUE CARBON(10A) IMPLANT?  
L29 QUE L27 AND L28  
L30 QUE L26 OR L29

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ACTIVATE STOPL7/A

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L31 QUE IMPLANT?(5A) (MASK# OR PHOTOMASK# OR RESIST# OR  
PHOTORESIST  
L32 QUE L31 AND (CMP OR POLISH? OR CHEMIPOLISH? OR CHEMIMECH? OR  
S  
L33 QUE L31 AND PLANARIZ?

L34                   QUE L32 OR L33  
L35                   QUE L34 AND (SIO OR SIO2 OR OXIDE# MONOXIDE# OR  
DIELECTRIC?  
L36                   QUE L34 AND (SOG OR PSG OR BSG OR PBSG OR BPSG OR USG OR FSG  
O  
L37                   QUE L34 OR L35 OR L36  
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L38                   3 S L30  
L39                   28 S L37